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**PATENT**  
**Atty. Docket No. MIT-106**  
**(5473/112)**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

APPLICANT: Michael Mermelstein  
SERIAL NO.: 09/274,601 GROUP NO.: 2878  
FILING DATE: March 23, 1999 EXAMINER David Spector  
TITLE: OPTICAL SYNTHETIC APERTURE ARRAY

**Assistant Commissioner for Patents  
Washington, D.C. 20231**

## **PRELIMINARY AMENDMENT**

Applicant hereby submits this preliminary amendment for entry in the above-referenced patent application.

**In the Claims**

06/22/2000 RGRADEN 00P00001 200531 09224501 Please Amend Claims 1-4, 7, 9, 11-13, and 19-21.

01 FC:103 1. <sup>18-00 CH</sup> An interferometric microlithography [synthetic aperture] system for producing a spatially non-periodic pattern [in a region of overlap] comprising:

a source of coherent electromagnetic radiation producing a plurality of coherent electromagnetic beams:

a plurality of beam controllers, each of said beam controllers positioned to receive a respective one of said plurality of said coherent electromagnetic beams and direct said respective coherent electromagnetic beam into a [said] region of overlap defined by an intersection of all of said plurality coherent electromagnetic beams; and